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	Application No.	Applicant(s)	
	10/032,542	ENDO ET AL.	
Notice of Allowability	Examiner	Art Unit	
	Daborah Chacko-Davis	1756	
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.			
1. This communication is responsive to <u>12/16/2003</u> .			
2. 🛚 The allowed claim(s) is/are <u>1-9</u> .			
3. 🛮 The drawings filed on <u>01/02/2002</u> are accepted by the Examiner.			
<ul> <li>4.  Acknowledgment is made of a claim for foreign priority un a)  All b)  Some* c)  None of the: <ol> <li>1.  Certified copies of the priority documents have</li> <li>2.  Certified copies of the priority documents have</li> <li>3.  Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)).</li> <li>* Certified copies not received:</li> </ol> </li> <li>Applicant has THREE MONTHS FROM THE "MAILING DATE" of noted below. Failure to timely comply will result in ABANDONMITHIS THREE-MONTH PERIOD IS NOT EXTENDABLE.</li> </ul>	been received. been received in Application No cuments have been received in this	national stage applica	
5. A SUBSTITUTE OATH OR DECLARATION must be submi INFORMAL PATENT APPLICATION (PTO-152) which give			IOTICE OF
6. CORRECTED DRAWINGS ( as "replacement sheets") must	t be submitted.		
(a) Including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached			
1)  hereto or 2) to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the	84(c)) should be written on the draw he header according to 37 CFR 1.121	ings in the front (not the (d).	e back) of
7. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.			
Attachment(s)	6 C N 11 (1 ( ) 1	Data da Arraba da COT	0.450)
1. Notice of References Cited (PTO-892)	5. Notice of Informal	• • • • • • • • • • • • • • • • • • • •	O-152)
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Summar Paper No./Mail Da	ate	
<ol> <li>Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No./Mail Date</li> </ol>	B), 7. ⊠ Examiner's Amend	Iment/Comment	
4. Examiner's Comment Regarding Requirement for Deposit	8. X Examiner's Statem	ent of Reasons for Allo	owance
of Biological Material	9.		
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4.10.

## **EXAMINER'S AMENDMENT**

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mr. Ramyar M. Farid on March 15, 2004.

The application has been amended as follows: Claim 8, line 2, after the word "aromatic" the word –compound-- has been inserted.

The preceding amendment was made to make the claim clear.

2. The following is an examiner's statement of reasons for allowance: Claims 1-5, are allowable over the prior art of record (U. S. Patent No. 6,280,898 (Hasegawa et al)) because the prior art of record fails to disclose a pattern formation method comprising forming a chemical amplified resist film wherein the resist includes a base polymer having a lactone group and having neither a hydroxyl group nor a carboxylic group, and an acid generator, and irradiating the resist film with a wavelength of a 1nm through 30nm band for pattern exposure. Claims 6-9, are allowable over the prior art of record (U. S. Patent No. 6,280,898 (Hasewaga et al)) because the prior art of record fails to disclose a pattern formation method comprising forming a chemically amplified resist film, the resist film including a base polymer, an acid generator, and an aromatic

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compound that does not generate acid during exposure, and irradiating the resist film with a wavelength of a 1nm through a 30nm band through a mask for exposure.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Daborah Chacko-Davis whose telephone number is (571) 272-1380. The examiner can normally be reached on M-F 9:30 - 6:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark F Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic

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Business Center (EBC) at 866-217-9197 (toll-free).

dcd

March 16, 2004.

MARK F. HUFF SUPERVISORY PATENT FXAMINED

TECHNOLOGY TEAMER TO THE

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